

ABSTRACT

A problem to be solved by the present invention is to provide an alloy that is suitable for a sputtering target material and easy to be produced by an atomization method, and, in order to solve the problem, the present invention provides an alloy containing: at least one selected from Co and Fe; B; C; and the balance being unavoidable impurities, wherein a concentration of C in the alloy is 50 ppm or more and 950 ppm or less, and wherein a composition of Co, Fe and B, excluding C and the unavoidable impurities, in the alloy is represented by the general formula: $(\text{Co}_X - \text{Fe}_{100-X})_{100-Y} - \text{B}_Y$, wherein X is 0 or more and 100 or less, and Y is 10 or more and 65 or less.

[No drawing]